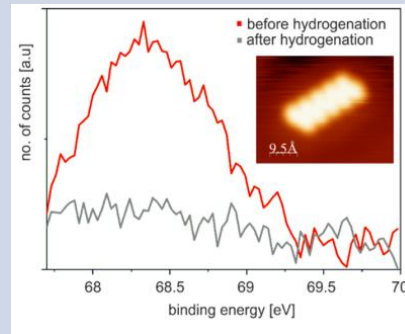


# Atomically precise surface cleaning

- The proposed technology is based on on-Surface synthesis of nanographene
- Scheme of the proposed technology:

Efficient cleaning (at atomic level) from halogens.  
Proven by LT-STM and XPS measurements



Technology Transfer proposal BSBF 2022

- For the original field of application, the technology was developed in the on-surface synthesis of nanographene.
  - This is a tool for surface cleaning from by-products of reactions (halogens: Br, Cl, F, I)
- The technology could have the following fields of application :  
electronics, pharmacy, optics

# Proposal SWOT Analysis

## Strengths

- Atomically precise cleaning from halogens
- Simple (thermal cracking of the molecular hydrogen)
- Very efficient

## Weaknesses

- Up to now, tested only on the surface
- UHV/HV conditions needed

## Opportunities

- Powder cleaning? Is it possible?

## Threats

- It is limited only for on surface?

- The IPR status of the technology is under patent application
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